

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error	Errors
1	IS&R	L1	4109	((359/290,291,295,298,302,311) or (73/720,721,722,723,715) or (216/2) or (438/53)).CCLS.	USP AT; US- PGP UB	2004 /08/ 11 13:2 5			0
2	BRS	L8	189	1 and @pd>20040401	USP AT; US- PGP UB	2004 /08/ 11 13:3 1			0
3	BRS	L9	141	8 and (sacrificial\$3 or psg or (phosposilicate adj glass) or polysilicon or silicon)	USP AT; US- PGP UB	2004 /08/ 11 13:3 1			0
4	BRS	L10	27	9 and transduc\$4	USP AT; US- PGP UB	2004 /08/ 11 13:3 1			0
5	BRS	L12	17	10 and (diaphragm or (silicon adj1 nitride) or (silicon adj1 dioxide))	USP AT; US- PGP UB	2004 /08/ 11 13:3 1			0
6	BRS	L14	12	12 and ((remov\$4 or etch\$4) near3 (sacrificial\$3 or psg or (phosposilicate adj glass) or polysilicon or silicon))	USP AT; US- PGP UB	2004 /08/ 11 13:3 2			0
7	BRS	L16	6	13 and void\$3	USP AT; US- PGP UB	2004 /08/ 11 13:3 2			0
8	BRS	L13	15	12 and ((remov\$4 or etch\$4) with (sacrificial\$3 or psg or (phosposilicate adj glass) or polysilicon or silicon))	USP AT; US- PGP UB	2004 /08/ 11 14:3 2			0
9	BRS	L20	0	12 and (re-flow\$4)	USP AT; US- PGP UB	2004 /08/ 11 14:3 5			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Corrections	Errors
10	BRS	L19	5	12 and (reflow\$4)	USP AT; US- PGP UB	2004 /08/ 11 14:3 5			0
11	BRS	L21	3	12 and (phosphosilicate or psg)	USP AT; US- PGP UB	2004 /08/ 11 14:3 7			0
12	BRS	L22	3	12 and (phosphosilicate or psg or (phosphor with silicate\$2))	USP AT; US- PGP UB	2004 /08/ 11 14:3 8			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Errors
1	BRS	L27	13605	(mems or (micro-electromechanic\$4) or (micro adj electr\$4 adj mechanic\$4))	USPAT; US-PGPUB ; EPO; JPO; DERWENT; IBM_TDB	2004 /08/ 11 15:1 5		0
2	BRS	L28	2120	27 and @pd>20040401	USPAT; US-PGPUB ; EPO; JPO; DERWENT; IBM_TDB	2004 /08/ 11 15:1 6		0
3	BRS	L29	1276	28 and (sacrificial\$3 or psg or (phosphosilicate adj glass) or polysilicon or (phosphor near3 silicate) or silicon)	USPAT; US-PGPUB ; EPO; JPO; DERWENT; IBM_TDB	2004 /08/ 11 15:1 7		0
4	BRS	L30	529	29 and (diaphragm or (silicon adj1 nitride) or (silicon adj1 dioxide))	USPAT; US-PGPUB ; EPO; JPO; DERWENT; IBM_TDB	2004 /08/ 11 15:1 7		0
5	BRS	L31	149	30 and transduc\$4	USPAT; US-PGPUB ; EPO; JPO; DERWENT; IBM_TDB	2004 /08/ 11 15:1 7		0
6	BRS	L32	116	31 and ((remov\$4 or etch\$4) with (sacrificial\$3 or psg or (phosphosilicate adj glass) or (phosphor near2 silicate) or polysilicon or silicon))	USPAT; US-PGPUB ; EPO; JPO; DERWENT; IBM_TDB	2004 /08/ 11 15:2 1		0
7	BRS	L33	26	32 and void\$3	USPAT; US-PGPUB ; EPO; JPO; DERWENT; IBM_TDB	2004 /08/ 11 15:2 2		0